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24 - 29 February 2008
San Jose Convention Center
San Jose, California, USA

Invitation to SPIE Advanced Lithography

The annual SPIE Advanced Lithography Symposium is a forum that brings together practitioners of the art of lithography into an exciting, informative, and very practical environment. This Symposium has a strong commitment to simultaneously support the interests of people working in semiconductor production lines, pilot lines, and research laboratories. It has been highly successful for the past 32 years because the programs in the five conferences are organized by users: those who are active in using technologies for production today or developing solutions for future production challenges. The numerous short courses are taught by instructors who are active in the field and are recognized for both theoretical knowledge and practical experience.

The SPIE Advanced Lithography Symposium is truly encompassing. It covers the state-of-the-art lithographic tools, resists, metrology, materials characterization, and design and process integration. It covers issues to be faced as we extend these technologies or try to switch to alternative technologies. This variety looms more important as optical lithography, historically the dominant patterning technology, becomes more difficult to apply to leading edge IC fabrication. The strength of the SPIE Advanced Lithography Symposium is the emphasis on presenting real data and applications. The Symposium is organized into five conferences:

- Emerging Lithographic Technologies
- Metrology, Inspection, and Process Control for Microlithography
- Advances in Resist Materials and Processing Technology
- Optical Microlithography
- Design for Manufacturability through Design-Process Integration

The oral presentations, poster sessions, and the panel discussions offer a wide range of topics and opportunities to interact with experts on specific subjects. Additional information is available from the many manufacturers' exhibits, which allow tool makers and material suppliers to showcase new products while interacting one-on-one with customers.

We welcome your participation and urge you to submit an abstract to the appropriate conference as described in the calls for papers. Relevant topics for new technology groups or panel discussions are also solicited.

Join us at the San Jose Convention Center, San Jose, California for the Advanced Lithography's 33rd year! We look forward to seeing you there!



Roxann L. Engelstad
Univ. of Wisconsin - Madison
2008 Symposium Chair



Christopher J. Progler
Photronics Inc.
2008 Symposium Co-Chair

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Enter keywords to find conferences with open calls for papers and submit an abstract.

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Announcements from Advanced Lithography 2007

The **Frits Zernike Award for Microlithography** is given annually for outstanding accomplishments in microlithographic technology, especially those furthering the development of semiconductor lithographic imaging solutions.

David M. Williamson, Nikon Research Corporation of America, USA, is the recipient of the 2007 Frits Zernike Award for Microlithography for his outstanding contributions to the advancement of imaging optics for microlithography.

The Microlithography Award is sponsored by ASML, Canon, Inc., and Cymer.



The **Diana Nyssonen Memorial Award for Best Paper of 2006** for the conference **Metrology, Inspection, and Process Control for Microlithography**

Awarded to Masafumi Asano, Takahiro Ikeda, Toru Koike, and Hideaki Abe, Toshiba Corp. (Japan)

For paper- In-line CD metrology with combined use of scatterometry and CD-SEM [6152-69]

Presented by Chas Archie, 2007 Conference Chair

The **2007 Best Student Paper Award** for the **Optical Microlithography**

Awarded to Neal V. Lafferty, Rochester Institute of Technology

For paper- Mask enhancement using an evanescent wave effect, Coauthors- **Jianming Zhou, Anatoly Bourov, Bruce W. Smith**, Rochester Institute of Technology

Presented by Donis G. Flagello, 2007 Conference Chair

This award was made possible by the generous sponsorship from



The **2006 C. Grant Willson Best Paper Award** for the **Advances in Resist Materials and Processing Technology** conference

Awarded to Gregory M. Wallraff, Carl E. Larson, Greg Breyta, Linda

Sundberg, D. Miller, IBM Almaden Research Ctr.; **Dario Gil, Karen Petrillo**, IBM Albany Nanotech; **W. Pierson**, ASML Netherlands B.V. (Netherlands)

For paper- **The effect of photoresist/topcoat properties on defect formation in immersion lithography** [6163-39]

Presented by **Qinghuang Lin**, IBM Thomas J. Watson Research Ctr. and **Clifford L. Henderson**, Georgia Institute of Technology
2007 Conference Chairs

This award was made possible by the generous sponsorship from



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